Freeform Search

Database:
```
US Pre-Grant Publication Full-Text Database
US Patents Full-Text Database
US OCR Full-Text Database
EPO Abstracts Database
JPO Abstracts Database
Derwent World Patents Index
IBM Technical Disclosure Bulletins
```

Term:
```
20020040847 and (etch$4 or pattern$4 or resist or
photoresist or mask or masking)
```

Display: `10` Documents in **Display Format:** `CIT` Starting with Number `1`

Generate: ○ Hit List ◉ Hit Count ○ Side by Side ○ Image

> [Search]   [Clear]   [Interrupt]

Search History

DATE: **Thursday, March 10, 2005**   Printable Copy   Create Case

Set Name side by side	Query	Hit Count	Set Name result set
DB=PGPB; PLUR=YES; OP=ADJ			
L3	20020040847 and (oxidiz$4 or oxidation)	1	L3
L2	20020040847 and (etch$4 or pattern$4 or resist or photoresist or mask or masking)	1	L2
L1	20020040847 and (kr or krypton or trench$2 or isolation or (gate adj (oxide or dielectric)))	1	L1

END OF SEARCH HISTORY

S11364	U	JPAB	(word adj line)	03-05 11:52:35
			(word adj line) same nitride	2005-03-05 11:51:08
S11363	U	JPAB	word adj line	2005-03-05 11:50:48
S11362	U	TDBD	(gate same (word adj lline))	2005-03-05 11:50:36
S11361	U	PGPB	(gate same (word adj lline))	2005-03-05 11:50:27
S11360	U	USPT	(gate same (word adj lline))	2005-03-05 11:50:19
S11359	U	PGPB,USPT	(20020040847 or 6391803) and ((gate adj insulation) or trench$2 or fox or isolation)	2005-03-03 15:20:13
S11358	U	PGPB,USPT	(20020040847 or 6391803) and (gate or trench$2 or fox or isolation)	2005-03-03 15:18:59
S11357	U	PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD	("sio.sub.2" or oxide or nitride or oxynitride or sion or sin) same densification same (("o.sub.2" or oxygen) adj plasma)	2005-03-03 14:06:10
S11356	U	PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD	("sio.sub.2" or oxide or nitride or oxynitride or sion or sin) same densification same plasma	2005-03-03 14:05:23
S11355	U	PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD	20050009281 and (cvd or lpcvd or pecvd)	2005-03-03 14:03:00
S11354	U	PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD	6649538 and (cvd or lpcvd or pecvd)	2005-03-03 14:01:36
S11353	U	PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD	(lpcvd adj 1	2005-

			(oxide or nitride or oxynitride or sion or sin or "sio.sub.2")) same (("o.sub.2" or oxygen) adj1 plasma) same (treating or treatment or exposing or exposure)	03-03 14:00:37
S11352	U	PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD	(cvd adj1 (oxide or nitride or oxynitride or sion or sin or "sio.sub.2")) same (("o.sub.2" or oxygen) adj1 plasma) same (treating or treatment or exposing or exposure)	2005-03-03 13:56:43
S11351	U	PGPB	20040147137 and ((ald or (atomic adj layer adj deposition)) same plasma)	2005-03-03 13:53:58
S11350	U	PGPB	20040147137 and (ald or (atomic adj layer adj deposition)) same plasma	2005-03-03 13:52:43
S11349	U	PGPB	20040166652 and (screen and plate and frame)	2005-03-03 10:35:25
S11348	U	PGPB	20030059690 and (frame and screen and plate)	2005-03-03 10:33:45
S11347	U	PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD	(flow adj path) same (frame near4 (screen or plate)) same (depression or opening or convacity or cavity) same groove$1	2005-03-03 10:29:18
S11346	U	PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD	((channel$1 or	2005-